

Transparent Niobium-doped titanium Dioxide Thin Films with high Seebeck coefficient for thermoelectric applications

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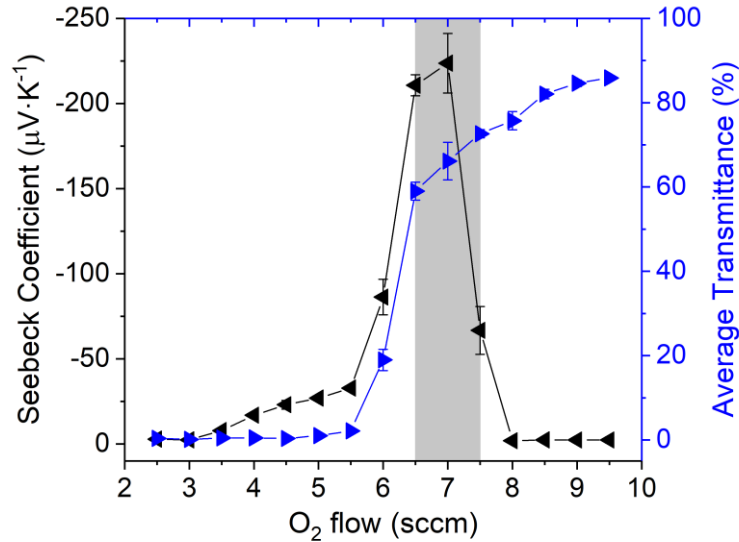


Figure 1 - Seebeck coefficient and average transmittance (400-700 nm) in relation to the Oxygen flow rate during deposition of TiO₂:Nb thin films deposited by reactive d.c. magnetron sputtering.

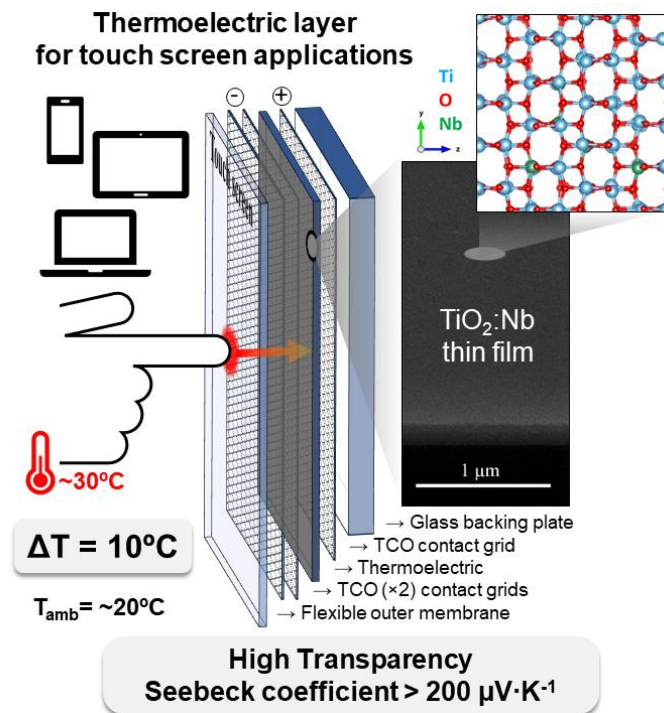


Figure 2 – Thermoelectric TiO₂:Nb thin films suitable for applications as transparent electrodes in photovoltaic systems and touch displays, amongst other devices.